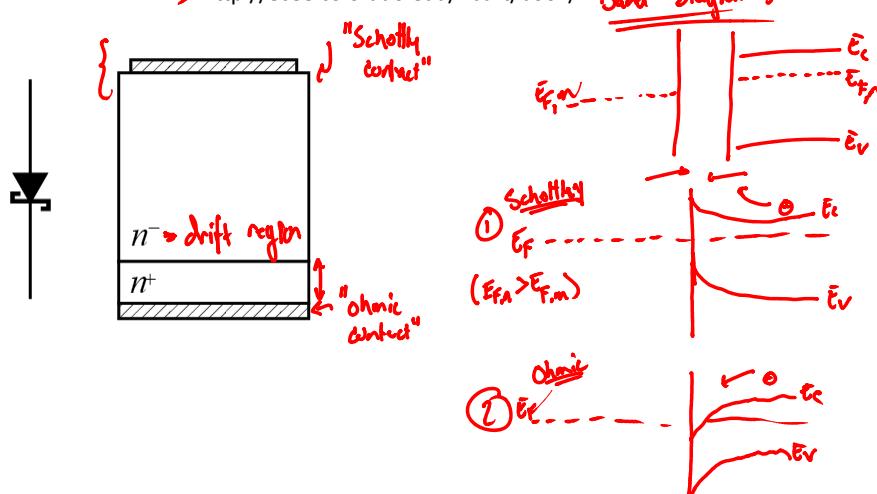




Semiconductor Electrostatics

Chapter 3.3

→ <http://ecee.colorado.edu/~bart/book/>



- The parameter ϕ_m is the metal work function (measured in volts),
- ϕ_s is the semiconductor work function,
- X is known as the electron affinity.

Table 9.1 | Work functions of some elements

Element	Work function, ϕ_m
Ag, silver	4.26
Al, aluminum	4.28
Au, gold	5.1
Cr, chromium	4.5
Mo, molybdenum	4.6
Ni, nickel	5.15
Pd, palladium	5.12
Pt, platinum	5.65
Ti, titanium	4.33
W, tungsten	4.55

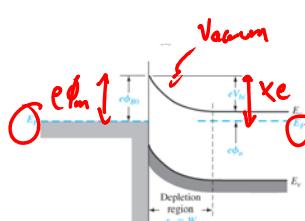


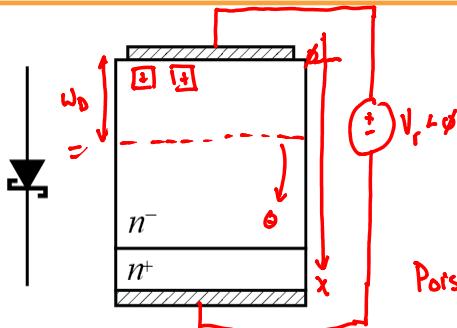
Figure 9.1 | (a) Energy-band diagram of a metal and semiconductor before contact; (b) ideal energy-band diagram of a metal-n-semiconductor junction for $\phi_m > \phi_s$.

Table 9.2 | Electron affinity of some semiconductors

Element	Electron affinity, X
Ge, germanium	4.13
Si, silicon	4.01
GaAs, gallium arsenide	4.07
AlAs, aluminum arsenide	3.5



Depletion Region



Goal: Determine how
• V_{BV}
• I_{on}
• C_d

depend on structure & their interdependence

Poisson's Equation:

$$\nabla^2 \psi = -\frac{\rho_f}{\epsilon} \quad \rho_f = \text{charge density}$$

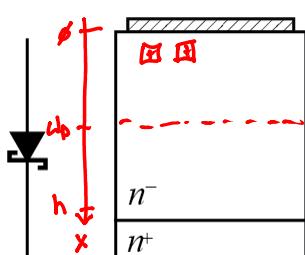
Laplace operator ψ = electric potential

$$Q_{tot} = q n_D w_D$$

- Assumptions:
- (1) Uniform in y & z
 - (2) Uniform doping throughout drift region n_D ($\frac{n}{\text{cm}^3}$)



Electric Field



Poisson's Equation in 1-D

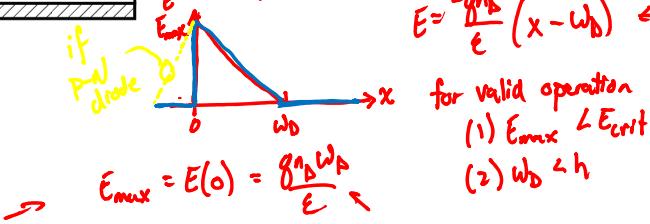
$$\frac{\partial^2 V}{\partial x^2} = -\frac{q n_D}{\epsilon}$$

$$E = \frac{\partial V}{\partial x} = \int_0^x -\frac{q n_D}{\epsilon} dx = -\frac{q n_D}{\epsilon} x + E_0$$

$$\text{Boundary condition } E(x=w_D) = 0$$

$$E = -\frac{q n_D}{\epsilon} (x - w_D)$$

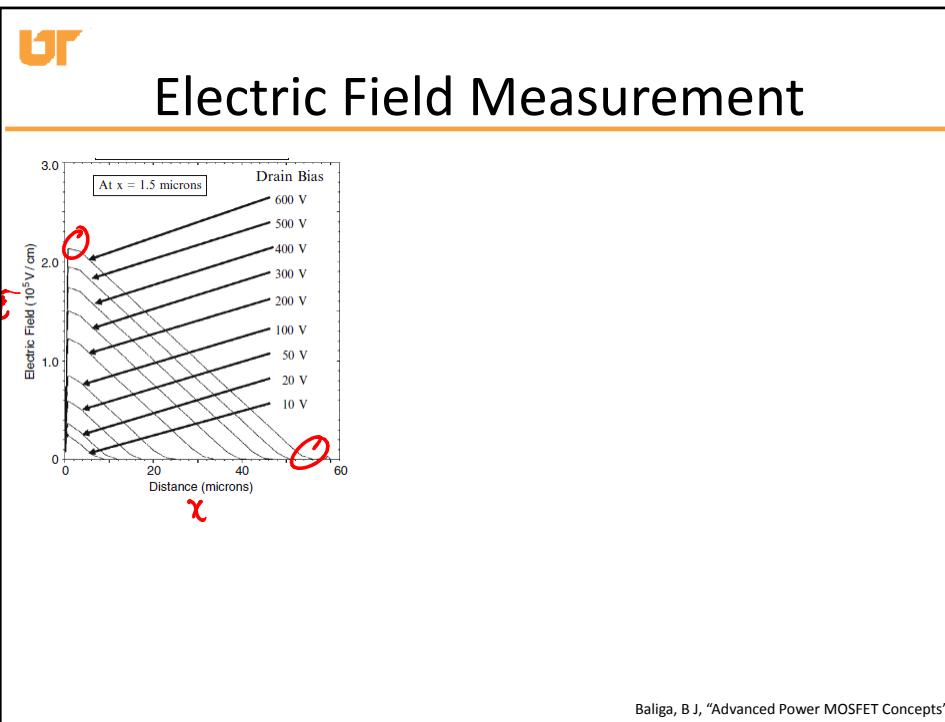
if P-N diode



$$E_{max} = E(0) = \frac{q n_D w_D}{\epsilon}$$

$$w_D = \frac{\epsilon E_{max}}{q n_D}$$

- for valid operation
(1) $E_{max} < E_{crit}$
(2) $w_D < h$



Baliga, B J, "Advanced Power MOSFET Concepts"

